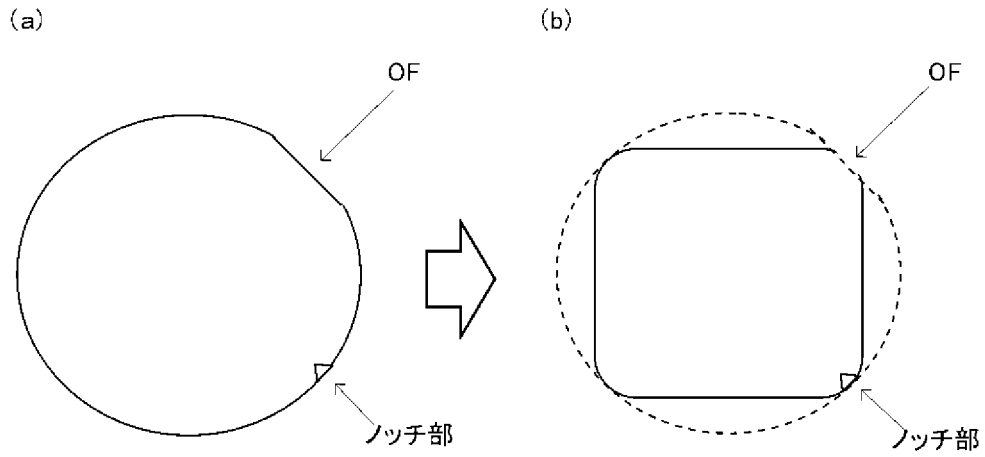
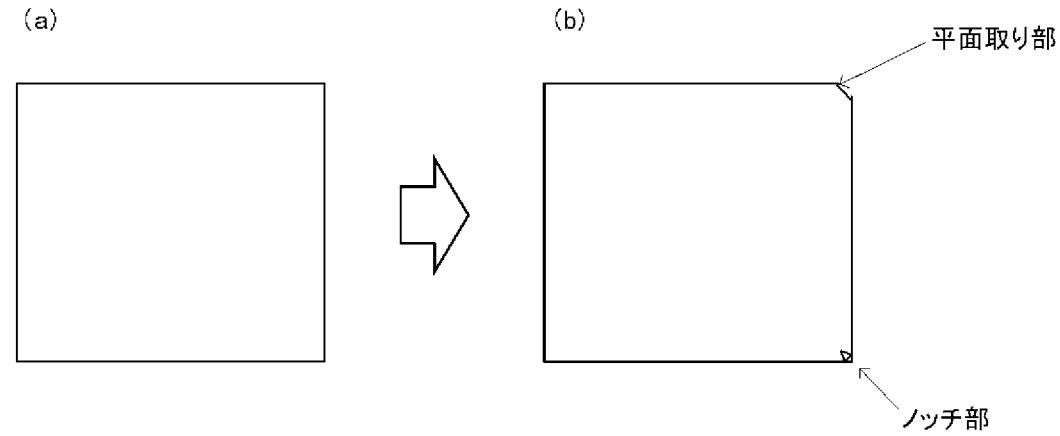
[図1]

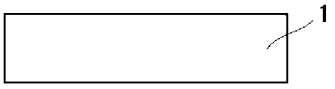


[図2]

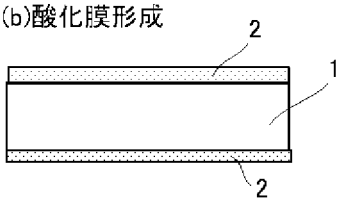


[図3]

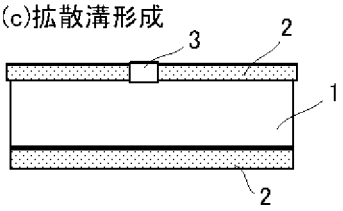
(a)基板



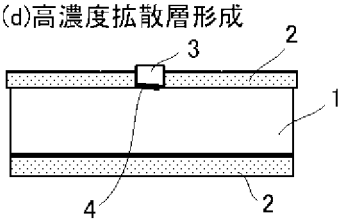
(b)酸化膜形成



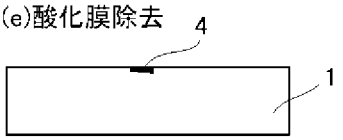
(c)拡散溝形成



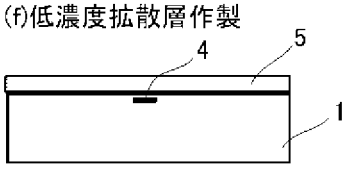
(d)高濃度拡散層形成



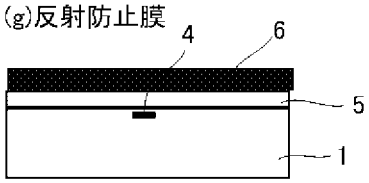
(e)酸化膜除去



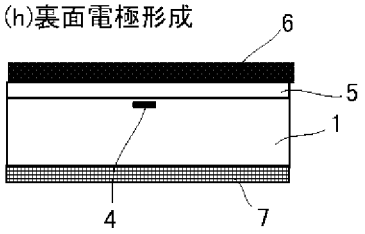
(f)低濃度拡散層作製



(g)反射防止膜



(h)裏面電極形成



(i)表面電極形成

